

What is claimed is:

Sub B17

1. A substrate treating method for cleaning a substrate by supplying a cleaning solution thereto, comprising the steps of: supplying said cleaning solution having ozone dissolved therein to said substrate; and irradiating said cleaning solution with ultraviolet light.
2. A substrate treating method for cleaning a substrate by supplying a cleaning solution thereto, comprising the steps of: irradiating said cleaning solution having ozone dissolved therein with ultraviolet light; and supplying said cleaning solution to said substrate.
3. A method as defined in claim 1, wherein said ultraviolet light has a wavelength in a range of 242.4 to 300nm.
4. A method as defined in claim 2, wherein said ultraviolet light has a wavelength in a range of 242.4 to 300nm.
5. A method as defined in claim 1, wherein said cleaning solution has a base added thereto.
6. A method as defined in claim 2, wherein said cleaning solution has a base added thereto.

Sub B1

Sub B1

7. A method as defined in claim 3, wherein said cleaning solution has a base added thereto.

5 8. A method as defined in claim 4, wherein said cleaning solution has a base added thereto.

Sub B2

10 9. A substrate treating apparatus comprising:
support means for supporting a substrate;
cleaning solution supply means for supplying a cleaning solution having ozone dissolved therein to said substrate; and
ultraviolet emitting means for emitting ultraviolet light to said substrate;

15 wherein, during a cleaning process in which said cleaning solution is supplied from said cleaning solution supply means to said substrate supported by said support means, said ultraviolet emitting means emits ultraviolet light to said cleaning solution supplied to said substrate.

20 10. An apparatus as defined in claim 9, wherein the ultraviolet light emitted from said ultraviolet light emitting means has a wavelength in a range of 242.4 to 300nm.

25 11. An apparatus as defined in claim 9, wherein said cleaning solution has a base added thereto.

Sub B1 12. An apparatus as defined in claim 10, wherein said cleaning solution has a base added thereto.

5 13. A substrate treating apparatus comprising:
support means for supporting a substrate;
ultraviolet emitting means for emitting ultraviolet light
to a cleaning solution having ozone dissolved therein before
said cleaning solution is supplied to said substrate; and
cleaning solution supply means for supplying said
10 cleaning solution irradiated with ultraviolet light to said sub-
strate supported by said support means.

14. An apparatus as defined in claim 13, wherein the ultra-
violet light emitted from said ultraviolet light emitting means
15 has a wavelength in a range of 242.4 to 300nm.

15. An apparatus as defined in claim 13, wherein said clean-
ing solution has a base added thereto.
20 16. An apparatus as defined in claim 14, wherein said clean-
ing solution has a base added thereto.

Sub a3 17. A substrate treating method for removing film from a
substrate by supplying a treating solution thereto, comprising
25 the steps of:

Sub a3
supplying said treating solution having ozone dissolved
therein to said substrate; and

irradiating said treating solution with ultraviolet light.

5 18. A substrate treating method for removing film from a
substrate by supplying a treating solution thereto, comprising
the steps of:

irradiating said treating solution having ozone dissolved
therein with ultraviolet light; and

10 supplying said treating solution to said substrate.

Sub B1
19. A method as defined in claim 17, wherein said ultraviolet
light has a wavelength in a range of 242.4 to 300nm.

15 20. A method as defined in claim 18, wherein said ultraviolet
light has a wavelength in a range of 242.4 to 300nm.

Sub B1
21. A method as defined in claim 17, wherein said treating
solution has a base added thereto.

20

22. A method as defined in claim 18, wherein said treating
solution has a base added thereto.

23. A method as defined in claim 19, wherein said treating
25 solution has a base added thereto.

24. A method as defined in claim 20, wherein said treating solution has a base added thereto.

25. A substrate treating apparatus for removing film from a substrate by supplying a treating solution thereto, comprising:

support means for supporting said substrate;
treating solution supply means for supplying said treating solution having ozone dissolved therein to said substrate;
and

10 ultraviolet emitting means for emitting ultraviolet light to said substrate;

wherein, during a film removing process in which said treating solution is supplied from said treating solution supply means to said substrate supported by said support means, said 15 ultraviolet emitting means emits ultraviolet light to said treating solution supplied to said substrate.

26. An apparatus as defined in claim 25, wherein the ultraviolet light emitted from said ultraviolet light emitting means 20 has a wavelength in a range of 242.4 to 300nm.

27. An apparatus as defined in claim 25, wherein said treating solution has a base added thereto.

25 28. An apparatus as defined in claim 26, wherein said treat-

Sub 31 ing solution has a base added thereto.

29. A substrate treating apparatus for removing film from a substrate by supplying a treating solution thereto, comprising:

5 support means for supporting said substrate;

ultraviolet emitting means for emitting ultraviolet light to said treating solution having ozone dissolved therein, before said treating solution is supplied to said substrate; and

10 treating solution supply means for supplying said treating solution irradiated with ultraviolet light to said substrate supported by said support means.

30. An apparatus as defined in claim 29, wherein the ultraviolet light emitted from said ultraviolet light emitting means

15 has a wavelength in a range of 242.4 to 300nm.

31. An apparatus as defined in claim 29, wherein said treating solution has a base added thereto.

20 32. An apparatus as defined in claim 30, wherein said treating solution has a base added thereto.